

	Hits	Search Text	DBs
1	6	((("5851701") or ("5242770") or ("6387596") or ("5476736") or ("5821034") or ("20020109827"))).PN.	USPAT; US-PGPUB
2	0	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$5 same (radial or tangential or oblique or quadrupol\$3 or annular) same (mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4)) same (resist or photoresist)) and (project\$4 same optic\$4 same polar\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	6	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same optic\$4 same polar\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	16	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7) and (polar\$7 same (pattern\$4 or pre\$2shape or pre\$2determin\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
5	18	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
6	1	("6738201").PN.	USPAT; US-PGPUB

	Hits	Search Text	DBs
7	6	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7) and radial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
8	13	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7) and (binary near4 \$5mask\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
9	0	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7 same wave\$4plat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
10	0	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7) and (polar\$7 same wave\$3plat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
11	2	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and (resist or photoresist) and (project\$4 same polar\$7) and (polar\$7 same wave\$3plat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	3	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (project\$4 same polar\$7) and ((immers\$3 or liquid) same (\$4lithograph\$7 or (projection near4 optic\$4) or expos\$4 or illuminat\$4 or irradiat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
13	2	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and ((resist or photoresist) same (negative or positive)) and (project\$4 same polar\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
14	15	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and (mask or reticle) and (project\$4 same polar\$7) and ((resist or photoresist) same (negative or positive))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
15	11	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same quadrupol\$3) and (mask or reticle) and (resist or photoresist) and (projection near4 optic\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
16	4	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and ((immers\$3 or liquid) same (\$4lithograph\$7 or (projection near4 optic\$4) or expos\$4 or illuminat\$4 or irradiat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	4	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and ((immers\$3 or liquid) same (\$4lithograph\$7 or (projection near4 optic\$4) or (project\$5 near4 lens) or expos\$4 or illuminat\$4 or irradiat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
18	81	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle)) and (resist or photoresist) and ((immers\$3 or liquid) same (\$4lithograph\$7 or (projection near4 optic\$4) or (project\$5 near4 lens) or expos\$4 or illuminat\$4 or irradiat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
19	37	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same (radial or tangential or oblique or quadrupol\$3 or annular)) and ((mask or reticle)) and (resist or photoresist) and ((immers\$3 or liquid) same (\$4lithograph\$7 or (projection near4 optic\$4) or (project\$5 near4 lens) or expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
20	1	((expos\$4 or illuminat\$4 or irradiat\$4) same polar\$7 same quadrupol\$3) and ((mask or reticle) same (phase\$2shift\$4 or (alternat\$4 near3 phase\$3shift\$4) or (chrome\$4 near3 phase\$3shift\$4))) and (resist or photoresist) and (projection near4 optic\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB